





# Increase in Cycling Stability of Doped LiNi<sub>0.5</sub>Mn<sub>1.5</sub>O<sub>4</sub>-Spinels during Charging between 2.0 and 5.0 V

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# **Motivation – Doping Elements**



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# Ru-Ti Doping – Synthesis





#### Ru-Ti vs. Fe-Ti Doping – Morphology





[A. Höweling, et al., J. Electrochem. Soc., 164, A6349-A6358 (2017)]

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# Ru-Ti vs. Fe-Ti Doping – Properties

Physical





#### Chemical

Material	Li <sup>1</sup>	Ni <sup>1</sup>	Mn <sup>1</sup>	Fe <sup>1</sup>	Ru¹	Ti <sup>1</sup>
	1.0	0.51	1.41	-	0.09	0.03
LNMRTO <sub>HT</sub>	1.0	0.51	1.40	-	0.09	0.03
	1.0	0.49	1.39	0.10	-	0.03
LNMFTO <sub>HT</sub>	1.0	0.49	1.39	0.10	-	0.03

- No change in granule size
- LNMRTO exhibits higher conductivity
- Bulk conductivity of HT higher than AP
- Chemical composition as targeted

13.01.2016

<sup>•</sup> Strong increase of particle size

<sup>&</sup>lt;sup>1</sup> data in mol



### **Ru-Ti vs. Fe-Ti Doping– Composition**



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#### Ru-Ti vs. Fe-Ti Doping – Electrochemistry





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#### **Mechanisms for capacity loss**





#### Ru-Ti doping – voltage profile (C/10)





# Ru-Ti doping – 2 V capacities in literature





2.7 V plateau depends on

- ordering
- doping
- morphology
- annealing temperature

criteria	LNMRuTO <sub>mod</sub>	LNMRuTO <sub>HT</sub>
ordering	(+)	(-)
morphology	truncated	octahedral
temperature	800 °C	1000 °C
2.7 V capacity	larger	smaller

#### These are only observations!



#### Ru-Ti doping – voltage profile



[A. Höweling, et al., J. Electrochem. Soc., 164, A6349-A6358 (2017)]



### Ru-Ti doping – in-situ XRD



• What is the reason for the voltage drop?

[ A. Höweling, et al., J. Electrochem. Soc., 164, A6349-A6358 (2017) ]

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#### **Ru-Ti doping - Model**



#### Conclusions



